Substitute for form 1449A/PTO

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Application Number 09/920,341			
Filing Dat	August 1, 2001		
First Named Inventor	Choi et al.		
Group Art Unit	1732		
Examiner Name	Tentoni, Leo B.		
Attorney Docket Number	UTS-17-07V06		

				U.S. PATENT DOCUMEN	TS	
Examiner Initials*	Cite No.	U.S. Patent Do	Kind Code ² (if known)	Name of Patentee or Applicant of Cited Document	Date of Publication of Cited Document MM-DD-YYYY	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
51	D1	4,326,805		Feldman et al.	04-27-1982	
9N	D2	4,724,222		Feldman et al.	02-09-1988	
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Attorney Docket Number	UTS-17-07V06			

OTHER PRIOR	R ART -	NON PATENT LITERATURE DOCUMENTS	-
Examiner Initials*	Cite No.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T ²
	D3	publisher, city and/or country where published. Feldman et al., "Wafer Chuck for Magnification correction in X-ray Lithography," Journal of Vacuum Science	
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OTHER PRIOR	R ART -	NON PATENT LITERATURE DOCUMENTS
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GN	В7	Norio Uchida et al., "A Mask-to-Water Alignment and Gap Setting Method for X-Ray Lithography Using Gratings" Journal of Vacuum Science and Technology, Part B, American Institute of Physics. New York, US, vol 9, no. 6, pages 3203-3204, November 1. 1991.
SN	88	White et al., "Novel alignment system for imprint lithography". 44 th International Conference on Electron, Ion, and Photon Beam Technology and Nanofabrication, Rancho Mirage, CA, USA, May 30-June 2, vol. 18, no. 6, pages 3552-3556, Journal of Vacuum Science and Technology, Part B, November 2000.
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Form PTO-1449 (modified) ATTY. DKT. NO. 5119-08301 SERIAL NO. 09/920,341 List of Patents and Publications O | PF@ Applicant's Information APPLICANT: Choi et al. **GROUP: 1724** Disclosure Statement se several sheets if necessary) FILING DATE: August 1, 2001 U.S. PATENT DOCUMENTS FILING DATE IF APPROPRIATE EXAM. DOCUMENT NUMBER DATE NAME **CLASS** SUB ALTHOUNG. DES. **CLASS** 4/1974 3,807,027 Heisler A1 A2 3,807,029 4/1974 Troeger 5/1974 **A3** 3,811,665 Seelig **A4** 4,062,600 12/1977 Wyse **A5** 4,098,001 7/1978 Watson **A6** 4,155,169 5/1979 Drake et al. Watson **A7** 4,202,107 5/1980 **A8** Sakawaki 4,267,212 5/1981 Α9 7/1982 De Fazio 4,337,579 A10 4,355,469 10/1982 Nevins et al. De Fazio A11 4,414,750 11/1983 A12 4,451,507 5/1984 Beltz et al. A13 4,610,442 9/1986 Oku et al. 沿 A14 4,694,703 11/1987 Routson (III) A15 4,731,155 3/1988 Napoli et al. A16 8/1988 Takei 4,763,886 A17 4,929,083 5/1990 Brunner A18 4,959,252 11/1990 Bonnebat et al. A19 5,072,126 12/1991 Progler A20 5,110,514 5/1992 Soane A21 5,126,006 6/1992 Cronin et al. A22 5,204,739 4/1993 Domenicali A23 8/1993 Boehnke et al. 5,240,550 A24 9/1994 5,348,616 Hartman et al. A25 2/1995 5,392,123 Marcus et al. Southwell et al. A26 5,425,964 6/1995 A27 9/1995 5,452,090 Progler et al. $\mathcal{S}\mathcal{N}$

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Form PTO-1449 (modified) List of Patents and Publications

For Applicant's Information

P Disclosure Statement

ATTY. DKT. NO. 5119-08301

SERIAL NO. 09/920,341

APPLICANT: Choi et al.

GROUP: 1724

FILING DATE: August 1, 2001

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Buermann et al.

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Form PTO-1449 (modified) ATTY. DKT. NO. 5119-08301 SERIAL NO. 09/920,341 List of Patents and Publications APPLICANT: Choi et al **GROUP: 1724** For Applicant's Information Disclosure Statement FILING DATE: August 1,2001 (Use several sheets if necessary) OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.) Stewart, D.; "A Platform with Six Degrees of Freedom", Proc. of Inst. Mech. Engrs., 1965, 180, 371-378. A69 *ها* A70 Paros, J.M.; Weisbord, L.; "How to Design Flexure Hinges", Machine Design, 1965, 151-156. Raibert, M.H.; Craig, J.J.; "Hybrid Position/Force Control of Manipulators", 1981, 102, 126-133. A71 A72 Hogan, Neville; "Impedance Control: An Approach to Manipulation", Journal of Dynamic Systems, Measurement and Control, 1985, 107, 1-7. Hollis, Ralph; Salcudean, S.E.; Allan, A.P.; "A Six-Degree-of-Freedom Magnetically Levitated Variable A73 Compliance Fine-Motion Wrist: Design, Modeling and Control", IEEE Transactions on Robotics and Automation, 1991, 7, 320-332. Tomita, Y. et al.; "6-Axes Motion Control Method for Parallel-Linkage-Type Fine Motion Stage", A74 Journal of Japan Society of Precision Engineering, 1992, 118-124. Slocum, Alexander; "Precision Machine Design: Macromachine Design Philosophy and its Applicability A75 to the Design of Micromachines", Proc. of IEEE Micro Electro Mech. Systems Workshop, 1992, 37-42. Krug, Herbert; Merl, Norbert; Schmidt, Helmut; "Fine Patterning of Thin Sol-Gel Films", Journal of A76 Non-Crystalline Solids, 1992, 447-450. Arai, T.; Larsonneur, R.; Jaya, Y.M.; "Calibration and Basic Motion of a Micro Hand Module", Proc. of A77 IECON, 1993, 1660-1665. Peng, Zhi-Xin; Adachi, N.; "Compliant Motion Control of Kinematically Redundant Manipulators", A78 IEEE Transactions on Robotics and Automation, 1993, 9, 831-837. Rong, Y.; Zhu, Y.; Luo, Z.; Liu, X.; "Design and Analysis of Flexure-Hinge Mechanism Used in Micro-A79 Positioning Stages", ASME, 1994, 2, 979-985. Hashimoto, M.; Imamura, Y.; "Design and Characteristics of a Parallel Link Compliant Wrist", IEEE A80 International Conference on Robotics and Automation, 1994, 2457-2462. A81 Merlet, J.P.; "Parallel Manipulators: State of the Art and Perspectives", Advanced Robotics, 1994, 8, 589-Ananthasuresh, S.; Kikuchi, N.; "Strategies for Systematic Synthesis of Compliant MEMS", ASME, A82 1994, 2, 677-686. Arai, T.; Tanikawa, T.; Merlet, J.P.; Sendai, T., "Development of a New Parallel Manipulator with A83 Fixed Linear Actuator ", Proc. of Japan/USA Symposium on Flexible Automation, 1996, 1, 145-149. A84 Howell, L.L.; Midha, A.; "Loop-Closure Theory of the Analysis and Synthesis of Compliant Mechanisms", Journal of Mechanical Design, 1996, 118, 121-125. Haisma, J. et al.; "Mold-Assisted Nanolithography: A Process for Reliable Pattern Replication", Journal of A85 Vacuum Science and Technology, 1996, 14, 4124-4128. Pernette, Eric; Henein, Simon; Magnani, Ivo; Clavel, Reymond; "Design of Parallel Robots in A86 Microrobotics", Robotica, 1997, 15, 417-420.

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